

a1
8. (Amended) The crosslinked resin as claimed in claim 1, characterized in that the acid is trifluoroacetic acid.

9. (Amended) The crosslinked resin as claimed in claim 1, characterized in that it additionally comprises at least one photoinitiating agent.

a2
12. (Amended) The process for the manufacture of ceramic or of glass as claimed in claim 10, characterized in that the simple metal alkoxides are zirconium alkoxide or titanium alkoxide.

a2
13. (Amended) The process for the manufacture of ceramic or of glass as claimed in claim 10, characterized in that it comprises a stage of preparation of complex metal alkoxides from lead carboxylate, zirconium alkoxide and titanium alkoxide.

14. (Amended) The process for the manufacture of ceramic or glass patterns at the surface of a substrate as claimed in claim 10, characterized in that:

- exposure to radiation is carried out through a mask, so as to define radiation-exposed patterns and non-radiation-exposed patterns;
- it comprises the dissolution of the non-radiation-exposed patterns in a solvent.

16. (Amended) The process for the manufacture of a ceramic or of a glass as claimed in claim 10, characterized in that the substrate is glass.

17. (Amended) The process for the manufacture of a ceramic or of a glass as claimed in claim 10, characterized in that the substrate is silicon.

a3
18. (Amended) A capacitor, characterized in that it is obtained from the process for the manufacture of a ceramic or of a glass as claimed in claim 10.

19. (Amended) A piezoelectric transducer, characterized in that it is obtained from the process for the manufacture of a ceramic or of a glass as claimed in claim 10.

20. (Amended) A ferroelectric memory, characterized in that it is obtained from the process for the manufacture of a ceramic or of a glass as claimed in claim 10.